L Number	Hits	Search Text	DB	Time stamp
1	137	TEOS and ozone and (SACVD or (sub adj3 atomic))	USPAT	2002/07/15 12:05
2	14	(TEOS and ozone and (SACVD or (sub adj3 atomic))) and porous	USPAT	2002/07/15 12:41
3	1122	TEOS same (ozone O3)	USPAT; US-PGPUB; EPO; JPO	2002/07/15 12:44
8	29	(TEOS same (ozone O3)) same mgm	USPAT; US-PGPUB; EPO; JPO	2002/07/15 13:23
13	8	"5804509"	USPAT; US-PGPUB; EPO; JPO	2002/07/15 13:25
18	0	"5804509" and carbon	USPAT; US-PGPUB; EPO; JPO	2002/07/15 13:27
23	0	"11" "097533"	JPO	2002/07/15 13:27
24	0	"097533"	JPO	2002/07/15 13:27

L Number	Hits	Search Text	DB	Time stamp
1	3836	(xerogel aerogel) and carbon	USPAT; US-PGPUB; EPO; JPO	2002/07/15 14:53
6	654	((xerogel aerogel) and carbon) and situ	USPAT; US-PGPUB; EPO; JPO	2002/07/15 14:54
11	351	(((xerogel aerogel) and carbon) and situ) and (oxygen O2)	USPAT; US-PGPUB; EPO; JPO	2002/07/15 14:54
16	351	(((xerogel aerogel) and carbon) and situ) and (oxygen O2)	USPAT; US-PGPUB; EPO; JPO	2002/07/15 14:55
21	149	((((xerogel aerogel) and carbon) and situ) and (oxygen O2)) and (SACVD porous)	USPAT; US-PGPUB; EPO; JPO	2002/07/15 14:55
26	6	(((((xerogel aerogel) and carbon) and situ) and (oxygen O2)) and (SACVD porous)) and TEOS and (ozone O3)	USPAT; US-PGPUB; EPO; JPO	2002/07/15 15:32
31	1	5103288.pn.	USPAT	2002/07/15 15:32
-	68546	hydrofluoric UDHF HF	USPAT; US-PGPUB; EPO; JPO	2002/07/13 20:59
-	70272	"oxide nitride oxide" ono	USPAT; US-PGPUB; EPO; JPO	2002/07/13 21:11
-	64235	"ammonia peroxide mixture" apm H2O2 "hydrogen peroxide"	USPAT; US-PGPUB; EPO; JPO	2002/07/13 21:08
-	21	(C4F8 ChF3) near etch$4	USPAT; US-PGPUB; EPO; JPO	2002/07/13 21:04
-	0	(hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide mixture" apm H2O2 "hydrogen peroxide") and ((C4F8 ChF3) near etch$4)	USPAT; US-PGPUB; EPO; JPO	2002/07/14 17:43
-	314	(C4F8 ChF3) same etch$4	USPAT; US-PGPUB; EPO; JPO	2002/07/13 21:04
-	0	(hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide mixture" apm H2O2 "hydrogen peroxide") and ((C4F8 ChF3) same etch$4)	USPAT; US-PGPUB; EPO; JPO	2002/07/13 21:06
-	77	(hydrofluoric UDHF HF) and ("oxide nitride oxide" ono) and ("ammonia peroxide mixture" apm H2O2 "hydrogen peroxide") and etch$4	USPAT; US-PGPUB; EPO; JPO	2002/07/13 21:06
-	1402	"ammonia peroxide mixture" apm	USPAT; US-PGPUB; EPO; JPO	2002/07/13 21:08
-	9	"ammonia peroxide mixture"	USPAT; US-PGPUB; EPO; JPO	2002/07/14 17:27
-	139	etch$4 near ("oxide nitride oxide" ono)	USPAT; US-PGPUB; EPO; JPO	2002/07/13 21:11
-	0	"ammonia peroxide mixture" and (etch$4 near ("oxide nitride oxide" ono))	USPAT; US-PGPUB; EPO; JPO	2002/07/13 21:12
-	0	("ammonia peroxide mixture" apm) and (etch$4 near ("oxide nitride oxide" ono))	USPAT; US-PGPUB; EPO; JPO	2002/07/13 21:13
-	15	("ammonia peroxide mixture" apm) and ("oxide nitride oxide" ono)	USPAT; US-PGPUB; EPO; JPO	2002/07/13 21:25
-	77370	"Hydrofluoric Acid" "Hydrogen fluoride" HF "Fluorohydric acid" "Fluoric acid" "Antisal 2B" "DEUTERIUMFLUORIDE"	USPAT; US-PGPUB; EPO; JPO	2002/07/13 21:27

-	31	((ammonia NH3) with (H2O2 "hydrogen peroxide")) with HF	USPAT; US-PGPUB; EPO; JPO	2002/07/14 20:47
-	26	"5308400"	USPAT; US-PGPUB; EPO; JPO	2002/07/14 20:47
-	2	5308400.pn.	USPAT; US-PGPUB; EPO; JPO	2002/07/14 21:20
-	206	HF and "anisotropic etching" and spacer and sidewall	USPAT; US-PGPUB; EPO; JPO	2002/07/14 21:22
-	184	(HF and "anisotropic etching" and spacer and sidewall) and gate	USPAT; US-PGPUB; EPO; JPO	2002/07/14 21:26
-	137	TEOS and ozone and (SACVD or (sub adj3 atomic))	USPAT	2002/07/15 12:05
-	14	(TEOS and ozone and (SACVD or (sub adj3 atomic))) and porous	USPAT	2002/07/15 12:41
-	1122	TEOS same (ozone O3)	USPAT; US-PGPUB; EPO; JPO	2002/07/15 12:44
-	29	(TEOS same (ozone O3)) same mgm	USPAT; US-PGPUB; EPO; JPO	2002/07/15 13:23
-	8	"5804509"	USPAT; US-PGPUB; EPO; JPO	2002/07/15 13:25
-	0	"5804509" and carbon	USPAT; US-PGPUB; EPO; JPO	2002/07/15 13:27
-	0	"11" "097533"	JPO	2002/07/15 13:27
-	0	"097533"	JPO	2002/07/15 14:52